

## ABSTRACT

A near-field exposure method including preparing a photomask for near-field exposure, having a light blocking film provided on a base material constituting a membrane portion and a support member supporting the base material, wherein a first alignment mark for rough alignment is provided on the support member and a second alignment mark for fine alignment is provided on the membrane portion, setting the photomask and an object to be exposed in a near-field exposure apparatus, aligning the photomask and the object using the first alignment mark, flexing the membrane portion to contact with the object and detecting a positional relation between the membrane portion and the object using the second alignment mark, aligning the photomask and the object based on the detected positional relation and flexing the membrane portion to contact with the object, and exposing the object to light from a light source by way of the photomask.